



6th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials /
7th International Conference on Plasma-Nano Technology & Science

ISPlasma2014/IC-PLANTS2014

March 2-6, 2014
Meijo University, Nagoya, Japan

Chairperson : Hirotaka Toyoda, Plasma Nanotechnology Research Center, Nagoya University
Vice-Chairperson : Nagahiro Saito, Nagoya University
Keiji Nakamura, Chubu University
Akihiro Wakahara, Toyohashi University of Technology

● Related Fields

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|-------------------------------|---|--|--|--|
| PLASMA SCIENCE | • Plasma Sources and Diagnostics
• Plasma for Nanotechnology | • Deposition and Modification of Thin Film
• Emerging Plasma Technology | • Etching Process | • PlasmaBio and Medicine |
| NITRIDE SEMICONDUCTORS | • Crystal Growth of GaN and Related Materials | • MBE Growth of Nitrides | • Characterization | • Device Processing |
| NANOMATERIALS | • Nanocarbon Materials
• Nanoparticles/Nanowires/Nanorods | • Porous Materials
• Nanomaterials for Energy Applications | • Surface Modification/Surface Functionalization | • Optical Devices
• Composite/Functionally Graded Materials
• Electrical Devices |

● Special Issue

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP).
Instruction for submitting papers will be informed by late December.

● Exhibition

During the symposium, enterprises and related organizations will exhibit at the venue.

Speakers

Plenary Speaker Makoto Konagai (Tokyo Institute of Technology, JAPAN)

Keynote Speakers

S. Fujimura (Tokyo Institute of Technology, JAPAN)
M. Hori (Nagoya University, JAPAN)
N. Otsuka (Panasonic Corporation, JAPAN)

H. Fujioka (The University of Tokyo, JAPAN)
H. Ohashi (AIST, JAPAN)
H. Tsukamoto (CONNEXX SYSTEMS Corporation, JAPAN)

W. G. (Bill) . Graham (Queen's University Belfast, UK)
Y. Okada (The University of Tokyo, JAPAN)
E. Yamaguchi (Doshisha University, JAPAN)

Invited Speakers

W. Choe (KAIST, KOREA)
H. Fukuyama (Tohoku University, JAPAN)
K. Itatani (Sophia University, JAPAN)
K. Kaneko (Shinshu University, JAPAN)
Y. Kumai (Toyota Central R&D Labs., INC., JAPAN)
M. Onomura (TOSHIBA America Electronic Components, Inc., USA)
J. Roepcke (Leibniz Institute for Plasma Science and Technology (INP Greifswald) , GERMANY)
K. Sasaki (Hokkaido University, JAPAN)
J.I. Shim (Hanyang University, KOREA)
M. Terrones (Shinshu University, JAPAN)
J.S. Wu (National Chiao Tung University, TAIWAN)

Y. Cordier (CNRS - CRHEA, FRANCE)
F. Fukuyo (Hamamatsu Photonics K.K., JAPAN)
M. Izawa (Hitachi Hi-Technologies Corporation, JAPAN)
D.G. Kim (KIMS, KOREA)
T.C. Lu (National Chiao Tung University, TAIWAN)
Y. Otogi (Hitachi Metals, Ltd., JAPAN)
R. Scaffaro (Palermo University, ITALY)
J.H. Shin (KAIST, KOREA)
J.Y. Tsao (Sandia National Laboratories, USA)

J.G. Duh (National Tsing Hua University, TAIWAN)
S. Ishizawa (Sophia University, JAPAN)
X. Jiang (The Chinese Academy of Sciences, CHINA)
I.C. Kizilyalli (Avogy Inc., USA)
T. Nakamura (ROHM Co., Ltd., JAPAN)
X. Pi (Zhejiang University , CHINA)
M. Sankaran (Case Western Reserve University, USA)
T. Setoyama (Mitsubishi Chemical Corporation, JAPAN)
H. Takao (Kagawa University, JAPAN)
C. Weisbuch (University of California / Ecole Polytechnique, USA / FRANCE)

Tutorial Speakers

U. Czarnetzki (Ruhr-Universität Bochum , GERMANY)
A. Toriumi (The University of Tokyo, JAPAN)

S. Kamiyama (Meijo University, JAPAN)
W. Walukiewicz (Solar Energy Materials Research Group, USA)

M. Nagatsu (Shizuoka University, JAPAN)

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors and Nanomaterials will be held on Sun, Mar 2, PM.

Focused Sessions

Power SiC/Nitride devices and Plasma collaboration / Industry-Academia Collaboration

Panel Discussion

How We Fire up the Innovation Engine? (II) - Towards the Establishment of Global Innovation Cluster - (Mar. 4)

<Moderator> E. Yamaguchi (Doshisha University, JAPAN)

Prospects of Solid State Lighting (Mar. 5)

<Moderator> S. Kamiyama (Meijo University, JAPAN)

Solution of energy problem using current generation Si, SiC and GaN based power devices (Mar. 6)

<Moderator> M. Kuzuhara (University of Fukui, JAPAN)

*Program and speakers listed above may change. *Listed in alphabetical order.

Registration

Please register on our website.

Advanced Online Registration is required.

Registration Fee :	General	Student
Early Registration (Before Jan 31, 2014)	JPY 40,000	JPY 10,000
Late Registration (Until Feb 20, 2014)	JPY 45,000	JPY 14,000
On-site Registration	JPY 50,000	JPY 18,000
Tutorial Fee :		
Participant in Main Symposium	JPY 5,000	JPY 2,000
Tutorial Registration Only	JPY 10,000	JPY 5,000
Banquet Fee (on March 4, 2014)	JPY 5,000	JPY 2,000

* Refunds cannot be made at any reason.

Sponsored by : The Japan Society of Applied Physics, ISPlasma2014 / IC-PLANTS2014 Organizing Committee

Co-sponsored by : Nagoya University, Nagoya Institute of Technology, Meijo University,
Chubu University, The Japan Society of Plasma Science and Nuclear
Fusion Research, The Japanese Association for Crystal Growth

Contact

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